

Notice of References Cited	Application/Control No. 10/824,313	Applicant(s)/Patent Under Reexamination CUI ET AL.	
	Examiner Khiem D Nguyen	Art Unit 2823	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,548,899	04-2003	Ross, Matthew	257/750
*	B	US-6,582,777	06-2003	Ross et al.	427/551
*	C	US-2003/0134039	07-2003	Ross et al.	427/255.28
*	D	US-5,266,815	11-1993	Sunami et al.	257/30
*	E	US-2004/0169281	09-2004	Nguyen et al.	257/758
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	S. Inaba et al. "Increase of Parasitic Resistance in Shallow P+ Extension with SiN Sidewall Process and Its Improvement by G Preamorphization for Sub-0.25 um pMOSFETs" IEEE Trans. Electr. Dev., Vol. 46, June 1999, pp. 1218-1224.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.